

Cee[®] 200CBX

Precision Coat-Bake System

The Cee[®] 200CBX precision coat-bake system combines a track quality precision spin coater with a high uniformity bake plate, in an efficient space saving design.



Serving the Semiconductor Industry Since 1987

Benefits

- ▶ Onboard Windows[®]-based PC control for enhanced interface capabilities and connectivity
- ▶ New compact design for minimized footprint
- ▶ Full-color, 7-inch touch screen display
- ▶ Teflon[®] spin bowl for maximum chemical compatibility
- ▶ Simultaneous operation and monitoring for both the coat and bake modules

Dimensions

- ▶ 28 in (71.1 cm) W × 19 in (48.3 cm) D × 12 in (30.5 cm) H
- ▶ Machine Weight: 165 lb (74.8 kg)
- ▶ Shipping Weight: 250 lb (113.4 kg)

Programmability

- ▶ Controlled by onboard Windows[®]-based PC
- ▶ Touch screen interface and display
- ▶ Ethernet port for network connectivity and uploading/downloading process parameters
- ▶ 250,000 process programs onboard
- ▶ Virtually unlimited steps per program
- ▶ 0.1-s resolution for step times with a range of 0 to 9,999.9 s/step
- ▶ Energy-saving capability (for predetermined temperature output control)
- ▶ Security: password protection available at no charge
- ▶ Three automated bake methods: contact, vacuum, proximity
- ▶ Bake plate auto sizing for 3-inch, 100-, 125-, 150-, and 200-mm substrates
- ▶ Temperature data recording
- ▶ Optional electronic lift pins (replace N₂ proximity for loading/unloading substrates from bake module). Program 1000 specific proximity heights above the surface in any sequence or combination. Height is programmed in 0.001-inch



Cee[®] 200CBX precision coat-bake system

- ▶ increments with an overall range of 0.000 to 0.750 inches.
- ▶ Ramping capability optional (8 specific set points within a single bake recipe)
- ▶ Spin speed: 0 to 6,000 rpm (12,000 rpm option at no charge; 16,000 rpm option available)
- ▶ Spin speed acceleration:
 - 0 to 30,000 rpm/s unloaded
 - 0 to 23,000 rpm/s for 200-mm substrate
 - 0 to 3,000 rpm/s for 6-inch × 6-inch × 0.250-inch photomask recessed chuck
- ▶ System capable of controlling third-party host software for high-end IDI/Cybor/Mykrolis positive displacement pumps
- ▶ Simultaneous dual automated dispense capability
- ▶ Bidirectional speed control/oscillating chuck
- ▶ Iteration software (recipe looping)
- ▶ Dispense or component outputs: 50
- ▶ In-process/dynamic speed/acceleration control

Precision

- ▶ Spin speed repeatability: within < 0.2 rpm
- ▶ Spin speed resolution: within < 0.2 rpm
- ▶ Substrate sizes: < 1 cm to 200 mm round; 7 inches × 7 inches square)
- ▶ Temperature resolution: ± 0.1°C
- ▶ Temperature range: ambient to 300°C (400°C optional)
- ▶ Temperature uniformity: 0.3% across working surface

Reliability

- ▶ Indirect drive system protects the spin motor from contact with process chemicals and solvents
- ▶ Vacuum and lid interlock
- ▶ Exceptional reliability and uptime
- ▶ 1-year full warranty on parts and labor
- ▶ Free remote technical support (phone, email, fax) for the life of the product
- ▶ Application process assistance for life of the product

Bowl & Exhaust Hood Design

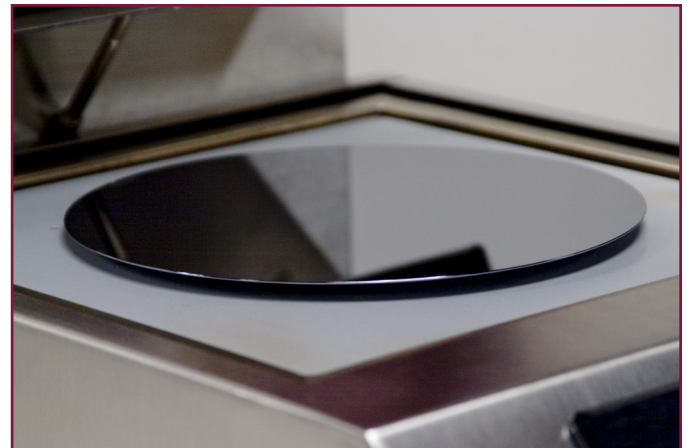
- ▶ All stainless steel construction
- ▶ Teflon® spin bowl for material compatibility
- ▶ Integrated bowl ring to eliminate material migration
- ▶ Optional stainless steel bowl (for all-stainless-steel construction)
- ▶ Optional polyethylene bowl (educational package) available
- ▶ Optional polyethylene liners available
- ▶ Optional polyethylene/Teflon® splash ring
- ▶ Closed and optional open lid designs for process flexibility
- ▶ Drain and exhaust ports located in the bottom of bowl
- ▶ Exhausted hood for removal of process chemicals
- ▶ Optional nitrogen purge for inert spin/bake environment

Utilities

- ▶ Voltage ranges: 100, 110–125, 208–240 VAC, 50/60 Hz
- ▶ Power requirements: 1793 watts (16 amps)
- ▶ Drain Port: ¾ inch OD
- ▶ Exhaust Port: 1 inch OD
- ▶ Vacuum: 20 to 25 inches Hg
- ▶ Bowl Exhaust: 20 to 50 cfm
- ▶ Bake Plate Exhaust: 1 inch OD; 5 to 10 cfm
- ▶ Nitrogen or CDA (for automated dispenses): 70 psi



Cee® 200CBX shown with optional nitrogen diffusers on the bake plate



Optional programmable lift pins on the bake plate (shown) allow for precise process control

©2017 Cost Effective Equipment, LLC. All statements, technical information and recommendations contained herein are based on tests we believe to be accurate, but the accuracy or completeness thereof is not guaranteed and the following is made in lieu of warranty expressed or implied. Neither the seller nor manufacturer shall be liable for any injury, loss or damage, direct or consequential, arising from the use or inability to use the product. Before using, user shall determine the suitability of the product for his intended use, and user assumes all risk and liability whatsoever in connection therewith. No statement or recommendation contained herein shall have any force or effect unless in an agreement signed by officers of the seller and manufacturer.

Windows is a registered trademark of Microsoft Corporation in the United States and other countries.
Teflon® and Delrin® are registered trademarks of E.I. du Pont de Nemours and Company.

F.6.6.7046.A Effective Date: 09/02/2010

